

Application Data Sheet

Application Information

Application Type: Regular

Subject Matter: Utility

Suggested Classification:

Suggested Group Art Unit:

CD-ROM or CD-R?: None

Title: Method Of Fabricating An Integral Capacitor And Gate Transistor Having Nitride And Oxide Polish St Layers Using Chemical Mechanical Polishing Elimination

Request for Early Publication?: No

Request for Non-Publication?: Yes

Suggested Drawing Figure:

Total Drawing Sheets: 7

Small Entity: No

Petition included?: No

Secrecy Order in Parent Appl.?: No

Applicant Information

Applicant Authority type: Inventor

Primary Citizenship Country: India

Status: Full Capacity

Given Name: Kunal N.

Family Name: Taravade

City of Residence: Portland

State or Province of Residence: Oregon
Country of Residence: USA
Street of mailing address: 15539 SE Knapp Dr.
City of mailing address: Portland
State or Province of mailing address: Oregon
Postal or Zip Code of mailing address: 97236

Applicant Information

Applicant Authority type: Inventor
Primary Citizenship Country: USA
Status: Full Capacity
Given Name: Gregory A.
Family Name: Johnson
City of Residence: Colorado Springs
State or Province of Residence: Colorado
Country of Residence: USA
Street of mailing address: 8830 Liverpool Lane
City of mailing address: Colorado Springs
State or Province of mailing address: Colorado
Postal or Zip Code of mailing address: 80920

Correspondence Information

Correspondence Customer Number: 24319

Representative Information

Representative Customer Number:	24319
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Domestic Priority Information

Application::	Continuity Type:	Parent Application:	Parent Filing Date:
This application	Division of	10/185,537	July 1, 2002

Assignee Information

Assignee name: LSI Logic Corporation

Street of mailing address: 1551 McCarthy Boulevard

City of mailing address: Milpitas

State or Province of
mailing address: California

Country of mailing address: USA

Postal or Zip Code of
mailing address: 95035